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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/715,264	11/17/2003	Nathan R. Brown	2269-4375.3US (99-1029.03	5086
	24247 7590 12/21/2006 TRASK BRITT		EXAMINER	
P.O. BOX 2550			MACARTHUR, SYLVIA	
SALT LAKE CITY, UT 84110			ART UNIT	PAPER NUMBER
			1763	
			MAIL DATE	DELIVERY MODE
			12/21/2006	PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

Advisory Action Before the Filing of an Appeal Brief

Application No.	Applicant(s)	
10/715,264	BROWN, NATHAN R.	
Examiner	'Art Unit	
Sylvia R. MacArthur	1763	

The MAILING DATE of this communication appears on the cover sheet with the correspondence address
THE REPLY FILED 11 December 2006 FAILS TO PLACE THIS APPLICATION IN CONDITION FOR ALLOWANCE.
1. The reply was filed after a final rejection, but prior to or on the same day as filing a Notice of Appeal. To avoid abandonment of this application, applicant must timely file one of the following replies: (1) an amendment, affidavit, or other evidence, which places the application in condition for allowance; (2) a Notice of Appeal (with appeal fee) in compliance with 37 CFR 41.31; or (3 a Request for Continued Examination (RCE) in compliance with 37 CFR 1.114. The reply must be filed within one of the following time periods:
a) The period for reply expires 3 months from the mailing date of the final rejection.
b) The period for reply expires on: (1) the mailing date of this Advisory Action, or (2) the date set forth in the final rejection, whichever is later. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of the final rejection. Examiner Note: If box 1 is checked, check either box (a) or (b). ONLY CHECK BOX (b) WHEN THE FIRST REPLY WAS FILED WITHIN TWO MONTHS OF THE FINAL REJECTION. See MPEP 706.07(f).
Extensions of time may be obtained under 37 CFR 1.136(a). The date on which the petition under 37 CFR 1.136(a) and the appropriate extension fee have been filed is the date for purposes of determining the period of extension and the corresponding amount of the fee. The appropriate extension fee under 37 CFR 1.17(a) is calculated from: (1) the expiration date of the shortened statutory period for reply originally set in the final Office action; or (2) a set forth in (b) above, if checked. Any reply received by the Office later than three months after the mailing date of the final rejection, even if timely filed may reduce any earned patent term adjustment. See 37 CFR 1.704(b). NOTICE OF APPEAL
2. The Notice of Appeal was filed on A brief in compliance with 37 CFR 41.37 must be filed within two months of the date of filing the Notice of Appeal (37 CFR 41.37(a)), or any extension thereof (37 CFR 41.37(e)), to avoid dismissal of the appeal. Since a Notice of Appeal has been filed, any reply must be filed within the time period set forth in 37 CFR 41.37(a). AMENDMENTS
3. The proposed amendment(s) filed after a final rejection, but prior to the date of filing a brief, will not be entered because
(a) They raise new issues that would require further consideration and/or search (see NOTE below);
(b) They raise the issue of new matter (see NOTE below);
(c) ☐ They are not deemed to place the application in better form for appeal by materially reducing or simplifying the issues for appeal; and/or
(d) ☐ They present additional claims without canceling a corresponding number of finally rejected claims.
NOTE: (See 37 CFR 1.116 and 41.33(a)).
4. The amendments are not in compliance with 37 CFR.1.121. See attached Notice of Non-Compliant Amendment (PTOL-324).
5 Applicant's reply has overcome the following rejection(s):
 Newly proposed or amended claim(s) would be allowable if submitted in a separate, timely filed amendment canceling th non-allowable claim(s).
7. For purposes of appeal, the proposed amendment(s): a) will not be entered, or b) will be entered and an explanation of how the new or amended claims would be rejected is provided below or appended. The status of the claim(s) is (or will be) as follows:
Claim(s) allowed: Claim(s) objected to:
Claim(s) rejected: 1-14.
Claim(s) withdrawn from consideration: AFFIDAVIT OR OTHER EVIDENCE
8. The affidavit or other evidence filed after a final action, but before or on the date of filing a Notice of Appeal will <u>not</u> be entered
because applicant failed to provide a showing of good and sufficient reasons why the affidavit or other evidence is necessary and was not earlier presented. See 37 CFR 1.116(e).
9. The affidavit or other evidence filed after the date of filing a Notice of Appeal, but prior to the date of filing a brief, will <u>not</u> be entered because the affidavit or other evidence failed to overcome <u>all</u> rejections under appeal and/or appellant fails to provide a showing a good and sufficient reasons why it is necessary and was not earlier presented. See 37 CFR 41.33(d)(1).
10. The affidavit or other evidence is entered. An explanation of the status of the claims after entry is below or attached. REQUEST FOR RECONSIDERATION/OTHER
11. The request for reconsideration has been considered but does NOT place the application in condition for allowance because: See Continuation Sheet.
12. ☑ Note the attached Information Disclosure Statement(s). (PTO/SB/08) Paper No(s). <u>herewith</u> 13. ☑ Other:
Syma R MacArthur
Patent Evaminer

Art Unit: 1763

Continuation of 11. does NOT place the application in condition for allowance because: The prior art of Saka et al teaches a method of endpoint detection in CMP wherein reflectance measurements are taken in-situ. The examiner wishes to clarify that Saka et al does teach a force gradient according to col.7 lines 13-40, analyzing the effect of the force gradient using reflectance measurement according to col. 7 lines 41-56, and feed forward process control wherein thr derived force gradient will be used on a subsequent wafer see col. 8 lines 4-35. Saka et al fails to topography as the basis of analysis. Sahotoa et al teaches analysis of the topography of a wafer to determine the progress of polishing, see col. 17 lines 18-27, The motivation to combine the teachings of Saka et al with Sahota et al is that topography is the basis of feed forward control rather than reflectance measurements. Sahota et al teaches that topographical measurements allows for the characterization of interlayer dielectric planarization taking into consideration the differences in thickness and patterns layer to layer within a wafer. Sahota et al teaches that modeling basis topography results in consistent uniform polishing results Nagahara et al also teaches a method for using wafer back pressure differentials see col. 6 lines 3-39. Lastly Korovin et al teaches a workpiece carrier with adjustable pressure zones and barriers. Note that the force gradients of Saka et al, Nagahara et al, or Korovin et al all teach a plurality of immediately adjacent distinctly different amounts of pressure. All fail to teach analysis of the polishing process using topography. Sahoto et al provides such a teaching so that a model of the polish process could be constructed leading to more uniform polishing products. Thus, each of the rejections of the previous action are maintained.